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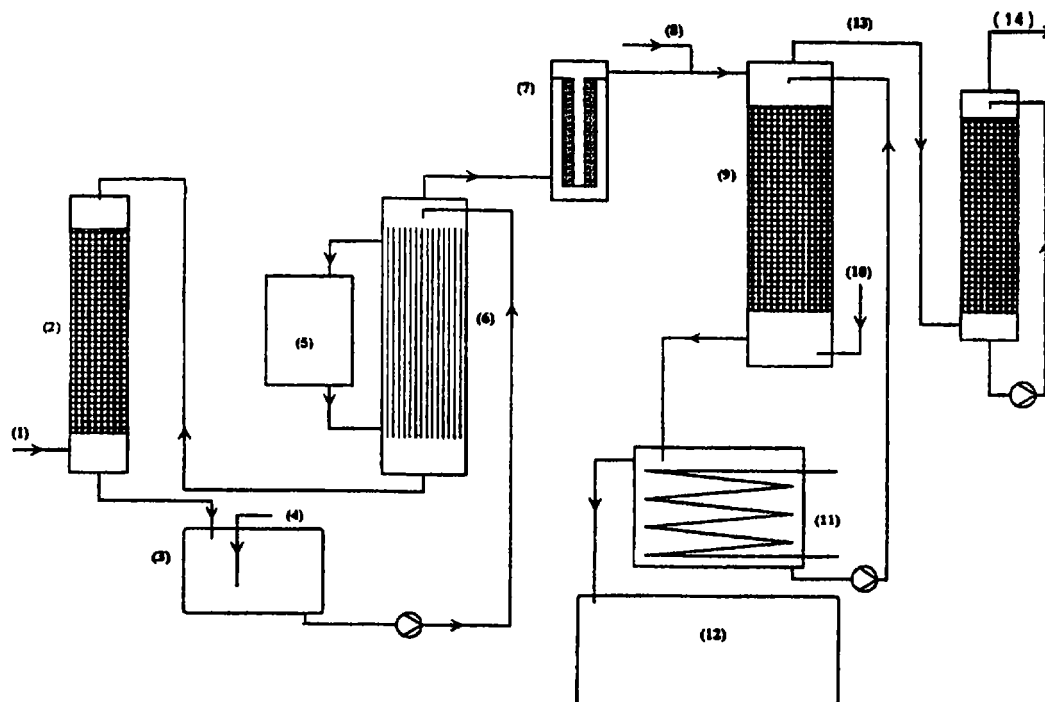
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(54) Title: METHOD FOR PRODUCING HIGH-PURITY SULPHURIC ACID

(54) Bezeichnung: VERFAHREN ZUR HERSTELLUNG HOCHREINER SCHWEFELSÄURE



(57) Abstract: The invention relates to a novel method for producing high-purity sulphuric acid for use in the semiconductor industry. The method comprises the addition of a hydrogen peroxide solution to an engineered column in order to reduce the SO₂ concentration, evaporation of the SO₃ and separation of acid traces. The high-purity SO₃ is then enriched with inert gas and the SO₃ is absorbed into sulphuric acid.

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For an explanation of the two-letter codes and the other abbreviations, reference is made to the explanations ("Guidance Notes on Codes and Abbreviations") at the beginning of each regular edition of the PCT Gazette.

(57) **Zusammenfassung:** Die vorliegende Erfindung betrifft ein neues Verfahren zur Herstellung von hochreiner Schwefelsäure für die Verwendung in der Halbleiterindustrie durch Zumischen einer Wasserstoffperoxidlösung zu einem Technischen Oelum zur Absenkung der SO₂-Konzentration, Verdampfung der SO₃, Abtrennung von Säurespuren. Anreicherung des hochreinen SO₃ mit Inertgas und Absorption des SO₃ in Schwefelsäure.